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(12) **United States Design Patent**
Ota et al.

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(54) **TOP PANEL FOR MICROWAVE INTRODUCTION WINDOW OF PLASMA PROCESSING APPARATUS**

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(73) Assignee: **Tokyo Electron Limited**, Tokyo (JP)

(**) Term: **14 Years**

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(30) **Foreign Application Priority Data**

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(52) **U.S. Cl.** **D15/138**; D15/199
(58) **Field of Classification Search** .... D7/586, D7/587, 501, 553.6, 600.4; D8/70, 74; D9/445, D9/454, 456; D15/133, 144.1, 199, 122, D15/138, 139; 117/103; 118/723 AN, 723 ME, 118/723 MP, 723 MW, 723 E, 723 ER; 216/69, 216/67; 257/E21.252, 252, 629, 631, E39.001; 427/562, 571, 575; D1/126, 128; D6/455; D13/122, 138, 139, 158–177, 182; D18/17; 156/242, 345; 175/374, 434; 204/298.38; 219/420–424, 523, 530, 541, 544; 264/328.14, 264/328.15, 328.16; 313/231.31; 315/111.21; 407/113–118; 408/145; 425/547–550, 564, 425/566, 570; 451/540–548; 700/121, 123
See application file for complete search history.

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(57) **CLAIM**

The ornamental design for a top panel for microwave introduction window of a plasma processing apparatus, as show and described.

DESCRIPTION

FIG. **1** is a front view of a top panel for microwave introduction window of plasma processing apparatus showing our new design;

FIG. **2** is a rear view thereof;

FIG. **3** is a right side view thereof;

FIG. **4** is a left side view thereof;

FIG. **5** is a top plan view thereof;

FIG. **6** is a bottom plan view thereof;

FIG. **7** is a sectional view taken along line **7**—**7** of FIG. **5**;

FIG. **8** is an enlarged view taken along line **8**—**8** of FIG. **7**;

FIG. **9** is an enlarged view taken along line **9**—**9** of FIG. **7**; and,

FIG. **10** is a perspective view thereof.

1 Claim, 4 Drawing Sheets

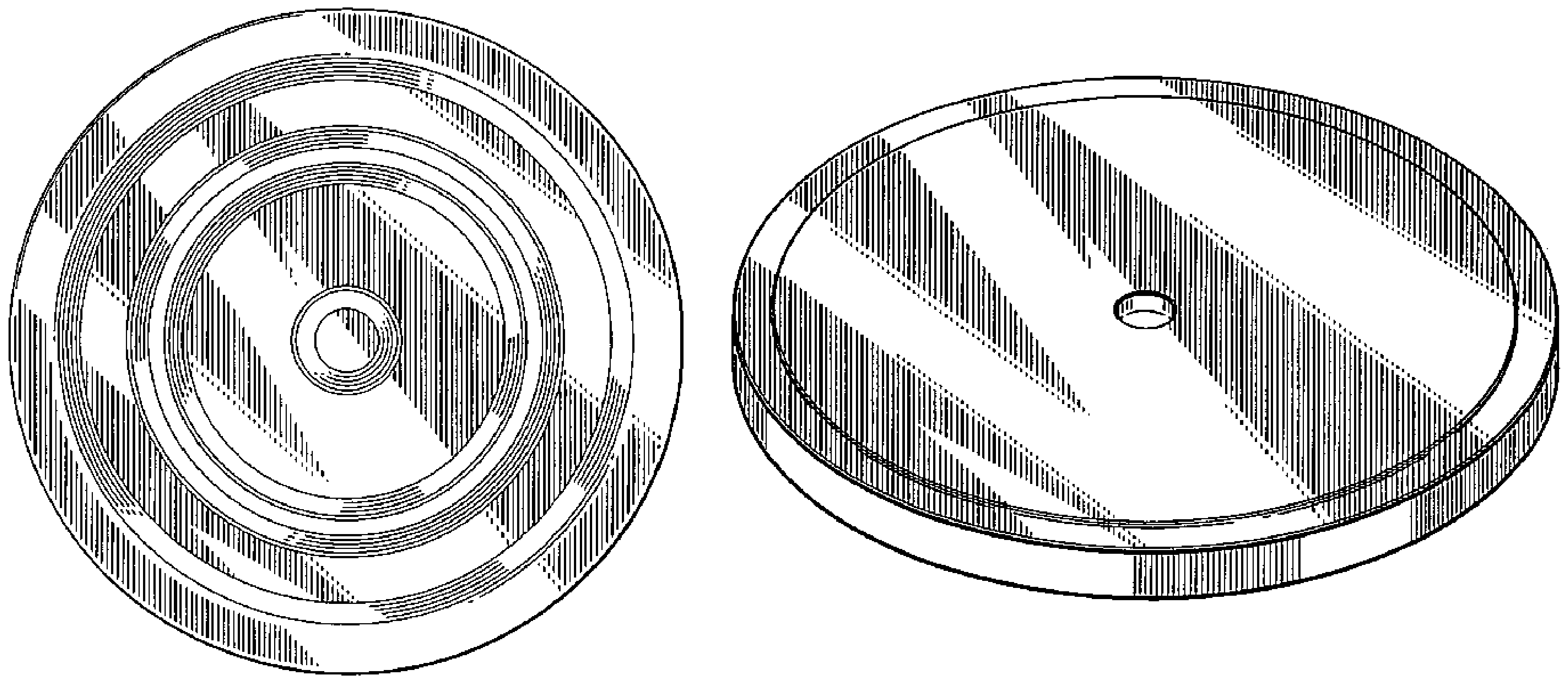

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FIG.1

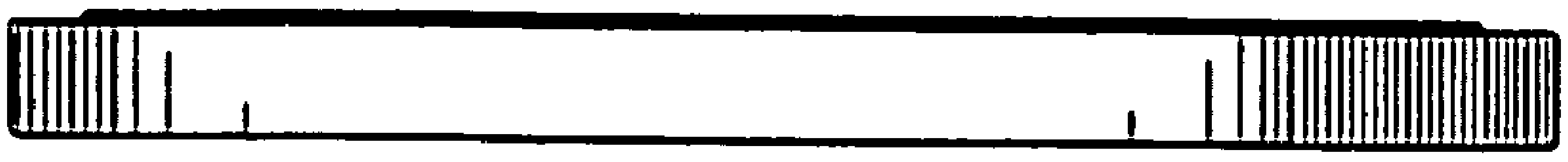

FIG.2

FIG.3

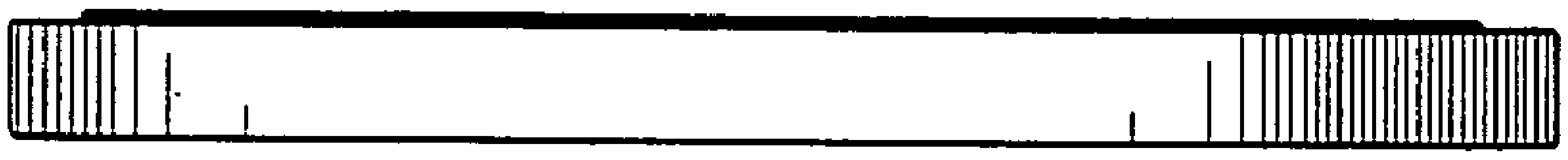

FIG.4

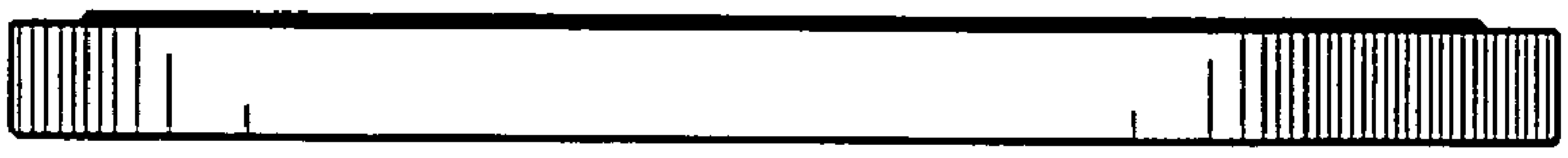

FIG.5

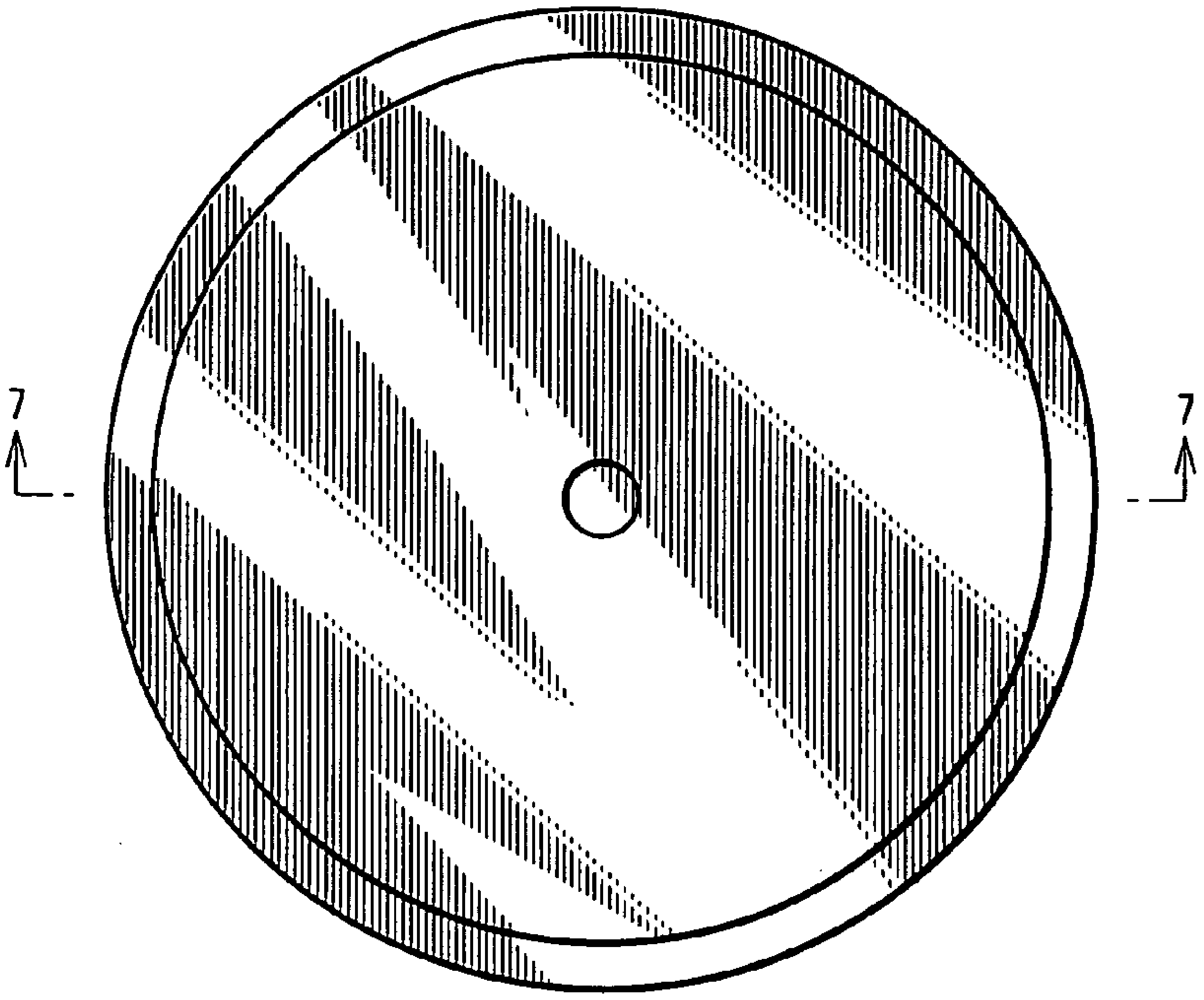

FIG.6

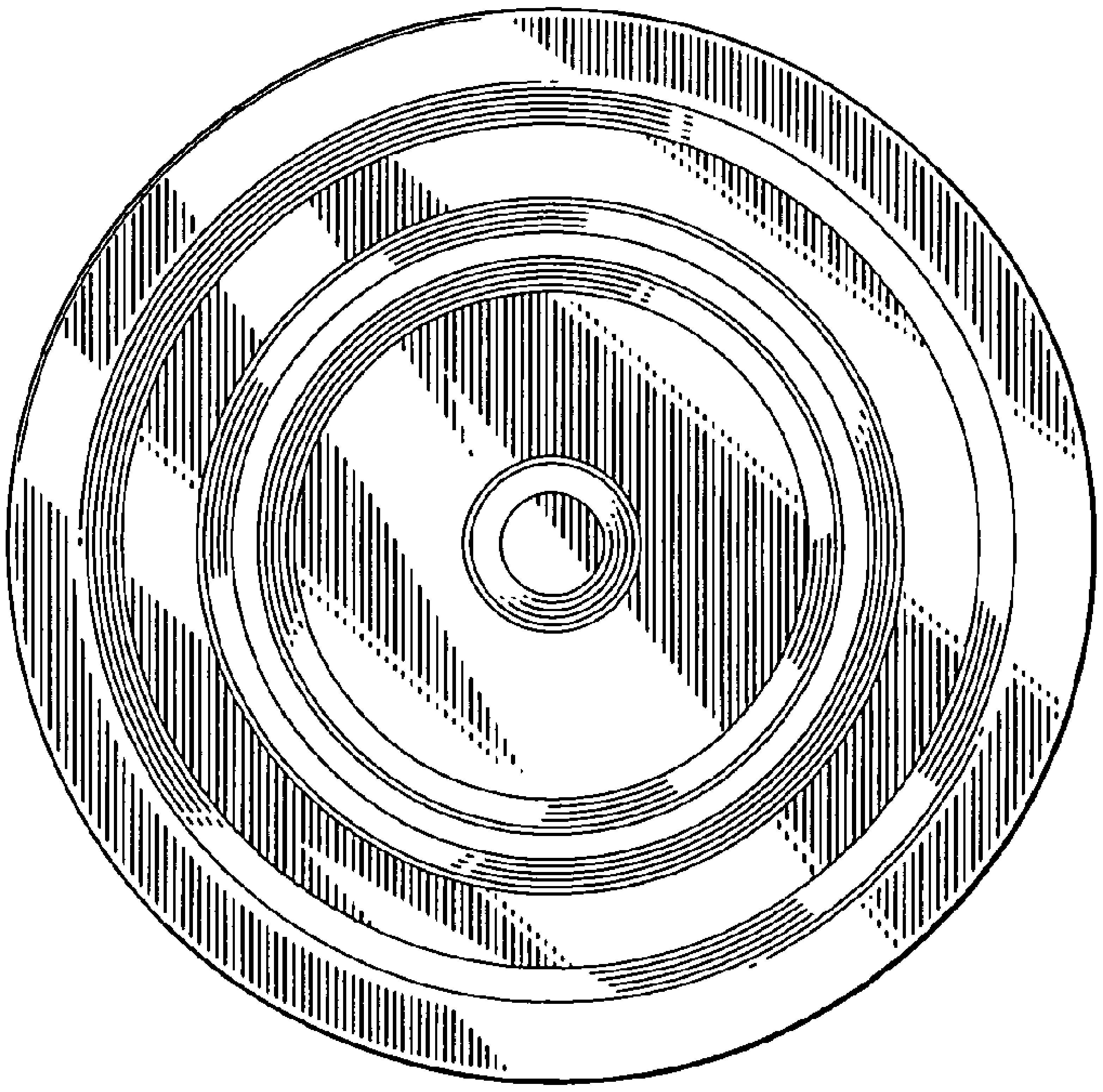

FIG.7

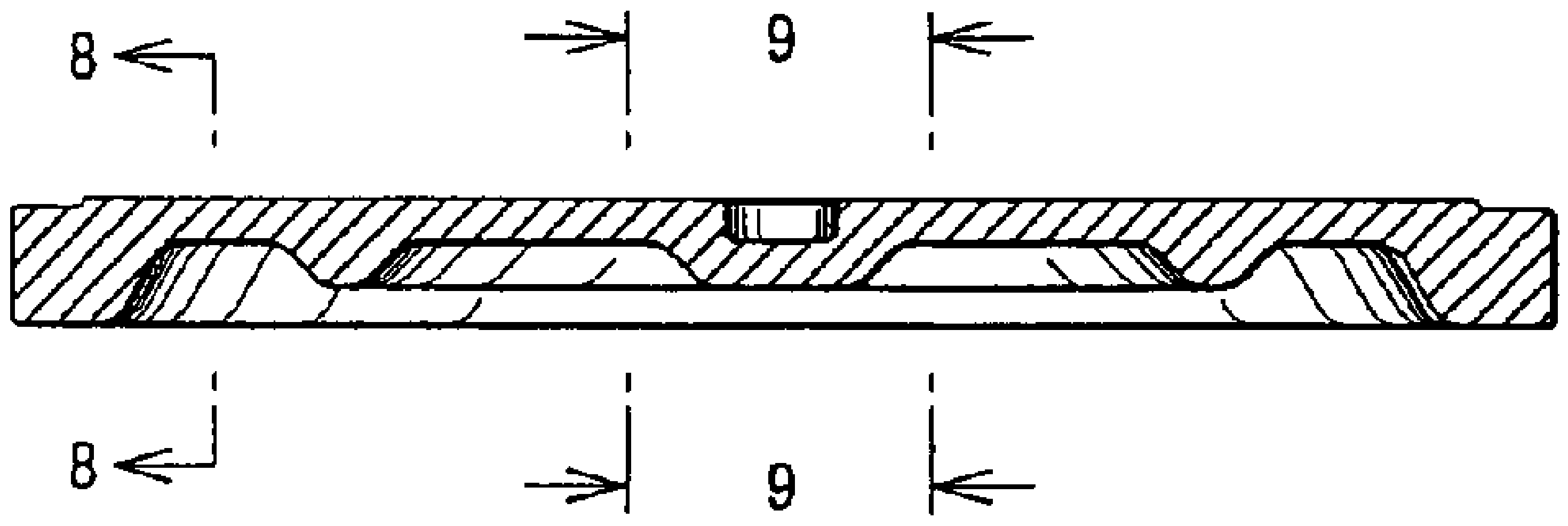

FIG.8

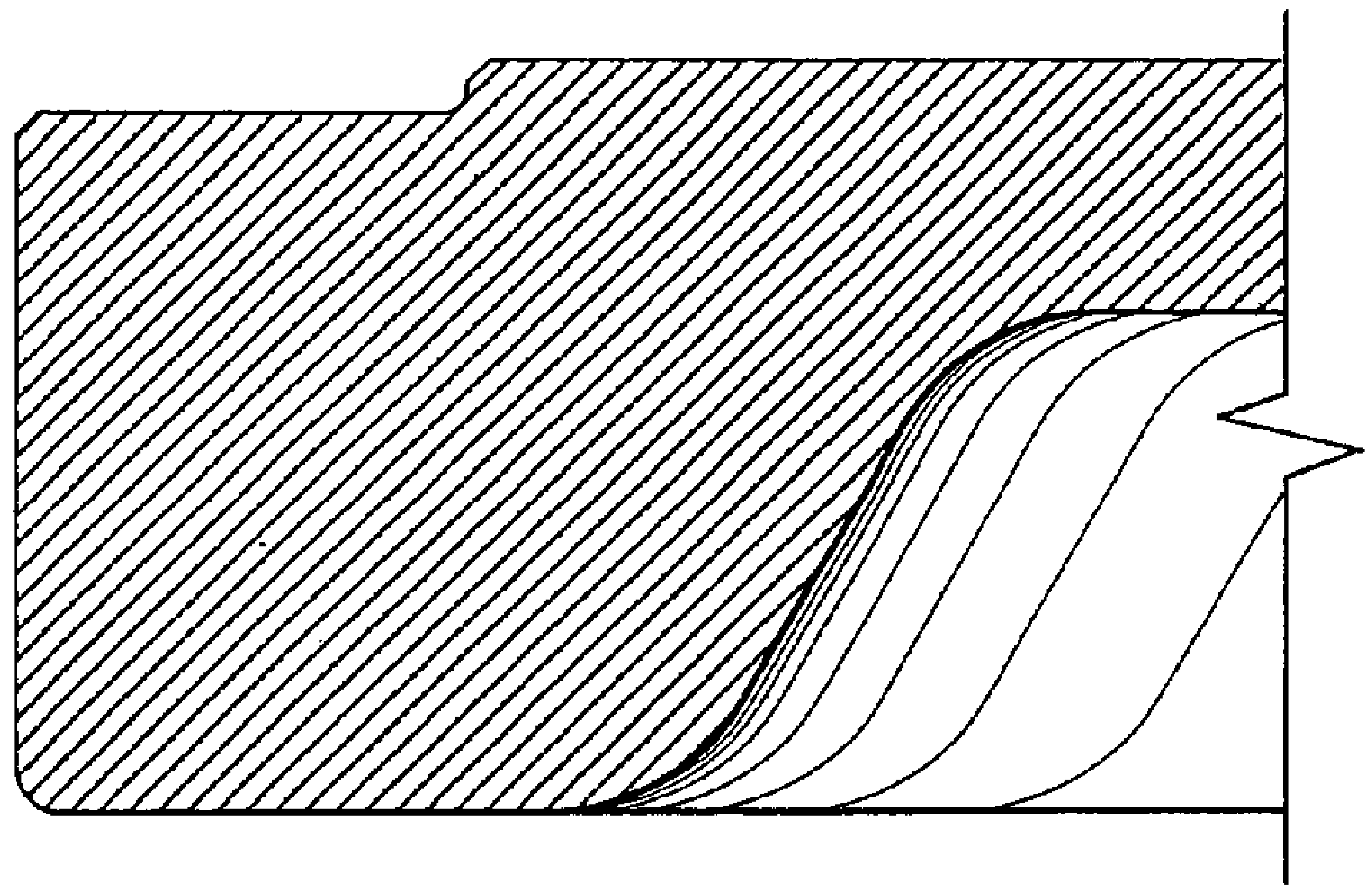

FIG.9

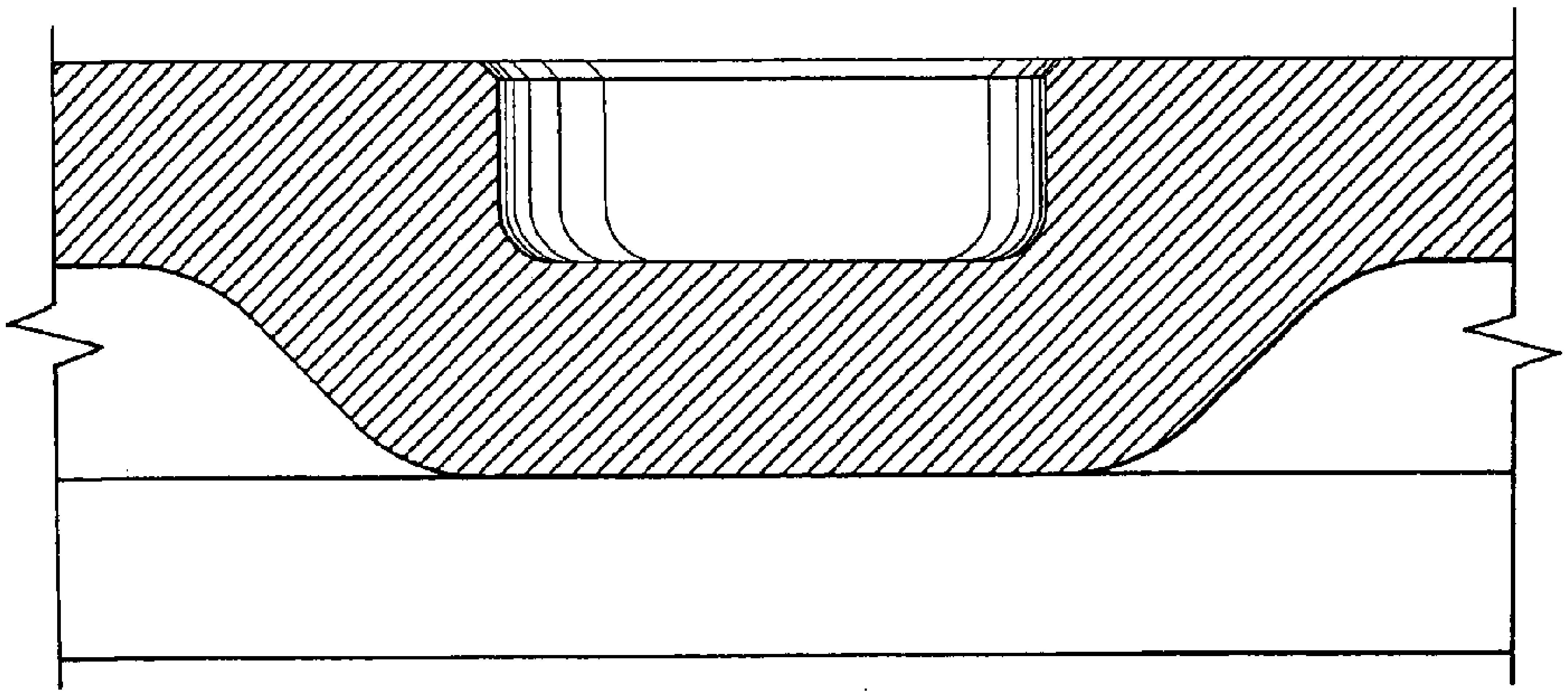

FIG.10